Amendments to the Claims:

The listing of claims will replace all prior versions and listings of claims in the application.

Listing of Claims:

- 1. (Currently Amended) A liquid injection module for a vapor liquid delivery system, said liquid injection module comprising:
- a liquid injector injecting configured to atomize liquid from a liquid source and making atomized said liquid source atomized to be an inject the atomized liquid source;
- a purging gas provider providing a purging gas to purge [[out]] from inside the liquid injector liquid from said liquid source that remains inside said liquid injector;
- a first three-way valve located between said liquid source, said purging gas provider, and said liquid injector, wherein said first three-way valve isolates said liquid source, said purging gas provider, and said liquid injector from a process gas; and

an exhausting branch disposing disposed adjacent said liquid injector, and said exhausting branch exhausting redundant liquid from said liquid source that is purged from the liquid injector by [[a]] said purging gas.

- 2. (Previously Presented) The liquid injection module according to claim 1, wherein said purging gas is selected from the group consisting of N₂ (nitrogen), CO₂, Ar and He.
- 3. (Currently Amended) The liquid injection module according to claim 1, further comprising a carrier gas provider to provide a carrier gas that carries earrying said atomized liquid source.
- 4. (Currently Amended) The liquid injection module according to claim [[3]] 1, wherein said liquid source is TMCTS (1,3,5,7, Tetramethylcyclotetrasiloxane; C₄H₁₆O₄Si₄.)

5. (Currently Amended) The liquid injection module according to claim 1, further comprising wherein said liquid injection module comprises a second three-way valve, said second three-way valve used to control flow between said exhausting branch and said liquid injector, wherein said second three-way valve is connected between said exhausting branch, a gas line, and a delivery line, and said gas line located between said liquid injector and said second three-way valve is used to control flow between said exhausting branch and said liquid injector.

6-7. (Cancelled)

- 8. (Currently amended) A heating injection apparatus for a vapor liquid delivery system [[used]] in a chemical vapor deposition (CVD) process, said heating injection apparatus comprising:
- a liquid injector_injecting configured to atomize liquid from a liquid source[[,]] and making inject the atomized liquid said liquid source atomized to be an atomized liquid source while said liquid source injecting;
- a purging gas provider providing a purging gas to purge [[out]] from inside the liquid injector liquid from said liquid source that remains inside said liquid injector;
- a first three-way valve located between said liquid source, said purging gas provider, and said liquid injector, wherein said first three-way valve isolates said liquid source, said purging gas provider, and said liquid injector from a process gas;

an exhausting branch disposed adjacent said liquid injector, and said exhausting branch exhausting redundant <u>liquid from</u> said liquid source that is purged <u>from the liquid injector</u> by said purging gas; and

- 9. (Previously Presented) The heating injection apparatus according to claim 8, wherein said purging gas is selected from the group consisting of N₂ (nitrogen), CO₂, Ar and He.
- 10. (Currently Amended) The heating injection apparatus according to claim 8, wherein said heating means is a thermostat device, wherein said thermostat device is selected from the group consisting of a heating coil and an infrared ray thermostat device.
- 11. (Cancelled)
- 12. (Currently Amended) The heating injection apparatus according to claim 8, wherein said liquid_source is TMCTS (1,3,5,7, Tetramethylcyclotetrasiloxane; C₄H₁₆O₄Si₄.)
- 13. (Currently Amended) The heating injection apparatus according to claim 8, further comprising a second three-way valve connecting connected between said exhausting branch, a gas line, and a delivery line, and wherein said gas line is a passageway that disposed between said liquid injector and said second three-way valve.
- 14. (Currently Amended) A heating injection apparatus for a vapor liquid delivery system [[used]] in a chemical vapor deposition (CVD) process, said heating injection apparatus comprising:
- a liquid injector injecting configured to atomize and inject a liquid from a source of liquid source and making said liquid source atomized to be an atomized liquid source while said liquid source injecting;

- a carrier gas provider providing a carrier gas to carry said atomized liquid source;
- a first three-way valve located between said liquid source, said purging gas provider and said liquid injector, wherein said first three-way valve isolates said liquid source, said purging gas provider, and said liquid injector from a process gas;

an exhausting branch disposed adjacent said liquid injector, and said exhausting branch exhausting redundant <u>liquid from</u> said liquid source that is purged <u>from the liquid injector</u> by said purging gas to prevent [[a]] polymerization around <u>in</u> said liquid injector;

a second three-way valve controlling flow between said exhausting branch and said liquid injector [[;]] connecting and connected between said exhausting branch, a gas line, and a delivery line, wherein said gas line is the defines a passage that located between said liquid injector and said second three-way valve, and said second three way valve controlling the flow between said exhausting branch and said liquid injector; and

a thermostat device located between said liquid injector and said carrier gas provider, said thermostat device heating said carrier gas, and said thermostat device is selected from the group consisting of a heating coil and an infrared ray thermostat device.

- 15. (Previously Presented) The heating injection apparatus according to claim 14, wherein said purging gas is selected from the group consisting of N₂ (nitrogen), CO₂, Ar and He.
- 16. (Currently Amended) The heating injection apparatus according to claim 14, wherein said liquid source is TMCTS (1,3,5,7, Tetramethylcyclotetrasiloxane; C₄H₁₆O₄Si₄.)
- 17. (Withdrawn) A method for a heat injection apparatus for a vapor liquid delivery system, said method comprising the steps of:

providing a liquid source;

purging out said liquid source remained inside a liquid injector by a purging gas; atomizing said liquid source to be an atomized liquid source after step of said purging out; injecting said atomized liquid source into a gas line;

exhausting said purging gas;

providing a carrier gas;

heating said carrier gas to the demanded production temperature before said carrier gas entering said gas line;

carrying said atomized liquid source through a delivery line into a gas-mixing device by said carrier gas; and

entering said atomized liquid source through a gas-mixing device into a reaction chamber to perform a deposition process.

- 18. (Withdrawn) The method according to claim 17, wherein said liquid source is TMCTS (1,3,5,7, Tetramethylcyclotetrasiloxane; C₄H₁₆O₄Si₄).
- 19. (Withdrawn) The method according to claim 17, wherein said purging gas is selected from the group consisting of N₂ (nitrogen), CO₂, Ar and He.
- 20. (Withdrawn) The method according to claim 17, wherein said carrier gas is He (helium).
- 21. (Withdrawn) The method according to claim 17, wherein the thermostat device of said heating said carrier gas comprises a heating coil.
- 22 (Withdrawn) The method according to claim 17, wherein the thermostat device of said heating said carrier gas comprises an infrared ray device.